

means for exhausting said gas in said chamber;
means for introducing gas into said chamber;
a power supply of Ultra High Frequency;
a microstrip antenna for radiating an electromagnetic wave, coupled to said power supply and installed in an atmosphere, said microstrip antenna comprising a discoidal electrode; and
a separation plate used as a dielectric between said antenna and the inside of said chamber.

35. (New) A dry etching apparatus according to claim 34, wherein said separation plate is a quartz disk.

36. (New) A dry etching apparatus according to claim 34, wherein said power supply supplies power of an Ultra High Frequency band having a frequency not less than 300MHz and not more than 1GHz.

REMARKS

Claims 10-33 have been cancelled without prejudice or disclaimer as a result of being withdrawn from consideration due to a restriction requirement. Additionally, claim 5 has been cancelled without prejudice or disclaimer. Applicants